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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/722,558	11/28/2003	Stefanie R. Chiras	YOR920030367US1 (20140/03	4980
30678 7	590 08/24/2005		EXAM	INER
CONNOLLY	BOVE LODGE & H	BOOTH, RICHARD A		
SUITE 800		ADDIE	DARRAM (DED	
1990 M STREET NW			ART UNIT	PAPER NUMBER
WASHINGTON, DC 20036-3425			2812	

DATE MAILED: 08/24/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
	10/722,558	CHIRAS ET AL.				
Office Action Summary	Examiner	Art Unit				
·	Richard A. Booth	2812				
The MAILING DATE of this communication Period for Reply	n appears on the cover sheet w	ith the correspondence address				
A SHORTENED STATUTORY PERIOD FOR R THE MAILING DATE OF THIS COMMUNICATI - Extensions of time may be available under the provisions of 37 C after SIX (6) MONTHS from the mailing date of this communication - If the period for reply specified above is less than thirty (30) days, - If NO period for reply is specified above, the maximum statutory of - Failure to reply within the set or extended period for reply will, by Any reply received by the Office later than three months after the earned patent term adjustment. See 37 CFR 1.704(b).	ON. FR 1.136(a). In no event, however, may a on. a reply within the statutory minimum of thi period will apply and will expire SIX (6) MO statute, cause the application to become A	reply be timely filed ty (30) days will be considered timely. NTHS from the mailing date of this communication. BANDONED (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on	06 June 2005.					
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<i>'</i> —	<u>-</u>					
· — · · · ·	closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.					
Disposition of Claims						
4) Claim(s) 1-30 is/are pending in the application 4a) Of the above claim(s) 23-30 is/are with 5) Claim(s) is/are allowed. 6) Claim(s) 1-22 is/are rejected. 7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction as	ndrawn from consideration.					
Application Papers		Ĺ				
9) The specification is objected to by the Exa	miner.					
10) The drawing(s) filed on is/are: a)	10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.					
Applicant may not request that any objection t	o the drawing(s) be held in abeya	nce. See 37 CFR 1.85(a).				
Replacement drawing sheet(s) including the c						
Priority under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for for a) All b) Some * c) None of: 1. Certified copies of the priority docu 2. Certified copies of the priority docu 3. Copies of the certified copies of the application from the International B * See the attached detailed Office action for	ments have been received. ments have been received in e priority documents have bee sureau (PCT Rule 17.2(a)).	Application No n received in this National Stage				
Attachment(s)	_					
1) Notice of References Cited (PTO-892)		Summary (PTO-413) (s)/Mail Date				
 2) Notice of Draftsperson's Patent Drawing Review (PTO-94 3) Information Disclosure Statement(s) (PTO-1449 or PTO/92) Paper No(s)/Mail Date <u>0205</u>. 	· · /	Informal Patent Application (PTO-152)				

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DETAILED ACTION

Election/Restrictions

Applicant's election of group I in the reply filed on 6/6/05 is acknowledged.

Because applicant did not distinctly and specifically point out the supposed errors in the restriction requirement, the election has been treated as an election without traverse (MPEP § 818.03(a)).

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States

Claims 1 and 3-14 are rejected under 35 U.S.C. 102(b) as being anticipated by Lu et al., EP 1 233 448.

Lu et al. shows the invention as claimed including a process for forming an electrically conductive metallic interconnect in a via in a dielectric which comprises: providing a dielectric layer (102,104) in a substrate wherein the substrate comprises electrically conductive copper lines 101, forming a trench or via 106,108 in the dielectric layer and exposing electrically conductive line in the substrate; depositing a first liner layer 124 comprising, for example, tantalum on the walls and bottom of the trench or via; removing residual contamination from the bottom of the trench or via using argon etching (see fig. 3C); depositing a second liner layer 126 of tantalum on the walls and

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the bottom of the trench or via; depositing a copper seed layer (see paragraph 0021) in the trench or via and filling the trench or via with electrically conductive material 118 such as copper (see figs. 3A-3F and paragraphs 0010-0022).

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 15-22 are rejected under 35 U.S.C. 103(a) as being unpatentable over Lu et al., EP 1 233 448 in view of Lopatin et al., U.S. Patent 6,893,955.

Lu et al. is applied as above but does not expressly disclose depositing an adhesion layer prior to depositing the first liner layer, and wherein residual contamination is removed from the bottom of the trench prior to depositing the first liner layer.

Lop atin et al. discloses forming an adhesion layer over exposed inner surfaces of a via (see col. 1-lines 55-61). In view of this disclosure, it would have been obvious to one of ordinary skill in the art at the time the invention was made to modify the device of Lu et al. so as to form an adhesion layer on the inner surfaces of the via because this will allow for good adhesion of subsequently deposited layers. With respect to residual contamination being removed from the bottom of the trench prior to depositing the first liner layer, the selection of any order of performing process steps is prima facie

obvious in the absence of new or unexpected results (see In re Burhans, 154 F.2d 690, 69 USPQ 330 (CCPA 1946)).

Claim 2 is rejected under 35 U.S.C. 103(a) as being unpatentable over Lu et al., EP 1 233 448 in view of Lee et al., U.S. Patent 6,486,059.

Lu et al. is applied as above but does not expressly disclose a low-K dielectric material having a dielectric constant of less than 3.9.

Lee et al. discloses forming an interlayer dielectric of a material such as SiLK which has a dielectric constant in the claimed range (see col. 2-lines 20-36). In view of this disclosure, it would have been obvious to one of ordinary skill in the art at the time the invention was made to modify the process of Lu et al. so as to form an interlayer dielectric of the claimed material because such an interlayer dielectric is a suitable material to be used in metallization processes.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Richard A. Booth whose telephone number is (571) 272-1668. The examiner can normally be reached on Monday-Thursday from 7:30-6:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Michael Lebentritt can be reached on (571) 272-1873. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Richard A. Booth Primary Examiner Art Unit 2812

August 22, 2005